

Title (en)
METHOD FOR ETCHING A COMPLEX PATTERN

Title (de)
VERFAHREN ZUM ÄTZEN EINES KOMPLEXEN MUSTERS

Title (fr)
PROCEDE DE GRAVURE D'UN MOTIF COMPLEXE

Publication
EP 2800722 A1 20141112 (FR)

Application
EP 13700005 A 20130103

Priority
• FR 1250098 A 20120105
• EP 2013050040 W 20130103

Abstract (en)
[origin: WO2013102637A1] A method for etching a desired complex pattern (50), in a first face of a substrate, comprising the following steps: - simultaneous etching of at least one first and one second sub-pattern through the first face of the substrate, the etched sub-patterns being separated by at least one separation wall, the width of the first sub-pattern being greater than the width of the second sub-pattern on the first face, and the depth of the first sub-pattern being greater than the depth of the second sub-pattern in a direction perpendicular to said first face, - a step of removing or eliminating said separation wall to reveal the desired complex pattern (50).

IPC 8 full level
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CPC (source: EP US)
B81C 1/00103 (2013.01 - EP US); **B81C 1/00531** (2013.01 - EP US); **B81C 1/00539** (2013.01 - EP US); **B81C 1/00619** (2013.01 - EP US); **H01L 21/3083** (2013.01 - EP US); **B81B 2203/033** (2013.01 - EP US); **B81B 2203/0392** (2013.01 - EP US); **B81C 2201/0132** (2013.01 - EP US); **B81C 2201/0133** (2013.01 - EP US); **B81C 2201/014** (2013.01 - EP US)

Citation (search report)
See references of WO 2013102637A1

Citation (examination)
US 2003139014 A1 20030724 - NAJAFI KHALIL [US], et al

Designated contracting state (EPC)
AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

DOCDB simple family (publication)
WO 2013102637 A1 20130711; CN 104039687 A 20140910; EP 2800722 A1 20141112; FR 2985602 A1 20130712; FR 2985602 B1 20140307; US 2014342557 A1 20141120; US 9187320 B2 20151117

DOCDB simple family (application)
EP 2013050040 W 20130103; CN 201380004918 A 20130103; EP 13700005 A 20130103; FR 1250098 A 20120105; US 201314370529 A 20130103